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During the data transfer between the XPS equipment and subsequent fitting routine an accidental shift of 13.48 eV to higher energies occurred in the binding energy scale relative to the experimental XPS spectra profile, and respective fit, for the O1s peak that is presented in Fig. 5(b). The authors apologize for this crude error and would like to acknowledge Dr. Victor Atuchin from the Laboratory of Optical Materials and Structures, Institute of Semiconductor Physics, Novosibirsk (Russian Federation) for its awareness. This correction does not change the results or discussion presented in this paper.

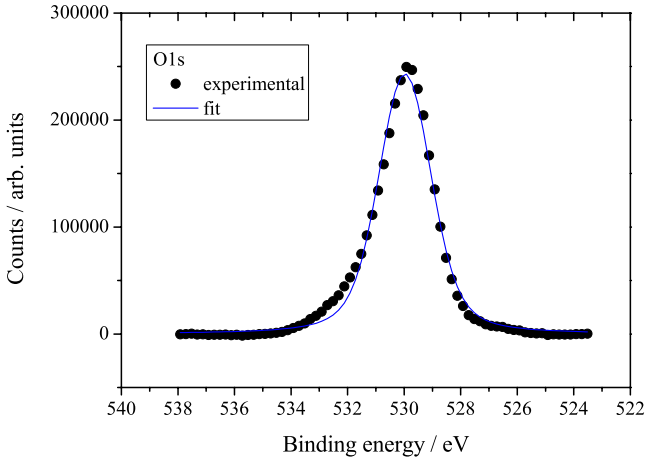


FIG. 5. (Color online) Simulation of the O1s XPS spectra profiles for the heavier N-doped sample in fig. 4 (sample NTiO13 with 1.19 at.% N), after background subtraction using a Shirley routine.

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